



Docket No.: 543822004700  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Siegfried SCHWARZL et al.

Application No.: 10/812,411

Confirmation No.: 1274

Filed: March 30, 2004

Art Unit: 1763

For: EUV LITHOGRAPHY SYSTEM AND CHUCK  
FOR RELEASING RETICLE IN A VACUUM  
ISOLATED ENVIRONMENT

Examiner: K. A. Moore

**AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION**

MS Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

**INTRODUCTORY COMMENTS**

This is in response to the non-final Office Action dated June 12, 2006, for which a response was due on September 12, 2006. Accordingly, this response is timely filed. Reconsideration and allowance of the pending claims, as amended, in light of the remarks presented herein are respectfully requested.

**Amendments to the Abstract** are reflected on page 3 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 4 of this paper.



**Amendments to the Drawings** begin on page 8 of this paper and include both an attached replacement sheet and an annotated sheet showing changes.

**Remarks/Arguments** begin on page 9 of this paper.

An **Appendix** including amended drawing figures is attached.